

(FILE 'HOME' ENTERED AT 08:48:51 ON 02 JUN 2003)

FILE 'REGISTRY' ENTERED AT 08:49:17 ON 02 JUN 2003

L1 0 S 2,2-THIODIETHANETHIOL
L2 20 S THIODIETHANETHIOL
L3 15 S TMXDI
L4 7440 S 1-15
L5 17 S DETDA

FILE 'USPATFULL, CAPLUS' ENTERED AT 08:54:40 ON 02 JUN 2003

L6 0 S 3524-66-1/RN AND 2778-41-8/RN AND 75389-89-8/RN
L7 0 S 3524-66-1/RN AND 2778-41-8/RN
L8 0 S 3524-66-1/RN AND 75389-89-8/RN
L9 157 S 3524-66-1/RN
L10 17 S L9 AND (ISOCYANATE OR DIISOCYANATE OR POLYISOCYANATE)
L11 6 S L10 AND (OPTICAL OR LENS)
L12 0 S 2778-41-8/RN AND 75389-89-8/RN
L13 3 S TMXDI AND DETDA AND (OPTICAL OR LENS)

=> d 1-3

L13 ANSWER 1 OF 3 USPATFULL

AN 2003:141093 USPATFULL
TI Impact resistant polyurethane and method of preparation
IN Nagpal, Vidhu J., Murrysville, PA, UNITED STATES
McDonald, William H., Cranberry Township, PA, UNITED STATES
Smith, Robert A., Murrysville, PA, UNITED STATES
PI US 2003096935 A1 20030522
AI US 2002-287880 A1 20021105 (10)
PRAI US 2001-332827P 20011116 (60)
DT Utility
FS APPLICATION
LN.CNT 1140
INCL INCLM: 528/044.000
NCL NCLM: 528/044.000
IC [7]
ICM: C08G018-00

L13 ANSWER 2 OF 3 USPATFULL

AN 2003:129997 USPATFULL
TI Light stable one-shot urethane-urea elastomers
IN Markusch, Peter H., McMurray, PA, United States
Cline, Robert L., Paden City, WV, United States
Pantone, Richard S., New Martinsville, WV, United States
Guether, Ralf, Pittsburgh, PA, United States
Sekelik, Thomas L., Carnegie, PA, United States
Haider, Karl W., McKees Rocks, PA, United States
PA Bayer Corporation, Pittsburgh, PA, United States (U.S. corporation)
PI US 6562932 B1 20030513
AI US 2001-976397 20011012 (9)
DT Utility
FS GRANTED
LN.CNT 1079
INCL INCLM: 528/058.000
INCLS 528/064.000; 528/085.000
NCL NCLM: 528/058.000
NCLS 528/064.000; 528/085.000

IC [7]
ICM: C08G018-10
EXF 528/58; 528/64; 528/85
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L13 ANSWER 3 OF 3 USPATFULL
AN 2000:131977 USPATFULL
TI Impact resistant polyurethane and method of manufacture thereof
IN Slagel, Edwin C., Avondale, AZ, United States
PA Simula Inc., Phoenix, AZ, United States (U.S. corporation)
PI US 6127505 20001003
AI US 1998-145658 19980902 (9)
RLI Continuation-in-part of Ser. No. US 1996-595262, filed on 1 Feb 1996,
now patented, Pat. No. US 5962617 which is a continuation-in-part of
Ser. No. US 1995-382562, filed on 2 Feb 1995, now abandoned
DT Utility
FS Granted
LN.CNT 575
INCL INCLM: 528/061.000
INCLS: 528/063.000; 528/064.000
NCL NCLM: 528/061.000
NCLS: 528/063.000; 528/064.000
IC [7]
ICM: C08G018-02
EXF 528/61; 528/63; 528/64
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

(FILE 'HOME' ENTERED AT 08:48:51 ON 02 JUN 2003)

FILE 'REGISTRY' ENTERED AT 08:49:17 ON 02 JUN 2003

L1 0 S 2,2-THIODIETHANETHIOL
L2 20 S THIODIETHANETHIOL
L3 15 S TMXDI
L4 7440 S 1-15
L5 17 S DETDA

FILE 'USPATFULL, CAPLUS' ENTERED AT 08:54:40 ON 02 JUN 2003

L6 0 S 3524-66-1/RN AND 2778-41-8/RN AND 75389-89-8/RN
L7 0 S 3524-66-1/RN AND 2778-41-8/RN
L8 0 S 3524-66-1/RN AND 75389-89-8/RN
L9 157 S 3524-66-1/RN
L10 17 S L9 AND (ISOCYANATE OR DIISOCYANATE OR POLYISOCYANATE)
L11 6 S L10 AND (OPTICAL OR LENS)

=> d 1-6

L11 ANSWER 1 OF 6 USPATFULL

AN 92:92892 USPATFULL
TI Hard transparent resins and process for the production thereof
IN Sasagawa, Katsuyoshi, Kanagawa, Japan
Kanemura, Yoshinobu, Kanagawa, Japan
Imai, Masao, Kanagawa, Japan
Suzuki, Toshiyuki, Kanagawa, Japan
PA Mitsui Toatsu Chemicals, Inc., Tokyo, Japan (non-U.S. corporation)
PI US 5166285 19921124
AI US 1992-835307 19920214 (7)
RLI Division of Ser. No. US 1989-362248, filed on 6 Jun 1989, now patented,
Pat. No. US 5104953
PRAI JP 1988-140484 19880609
DT Utility
FS Granted
LN.CNT 913
INCL INCLM: 526/288.000
INCLS: 526/301.000
NCL NCLM: 526/288.000
NCLS: 526/301.000
IC [5]
ICM: C08F012-30
EXF 526/301; 526/288
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L11 ANSWER 2 OF 6 USPATFULL

AN 92:34245 USPATFULL
TI Radiation-curable liquid resin for secondary coating of lightwave
guides
IN Birkle, Siegfried, Hoechststadt A/Aisch, Germany, Federal Republic of
Feucht, Hans-Dieter, Erlangen, Germany, Federal Republic of
Kamps, Rainer, Coburg, Germany, Federal Republic of
Rissel, Eva, Forchheim, Germany, Federal Republic of
PA Siemens Aktiengesellschaft, Berlin & Munich, Germany, Federal Republic
of (non-U.S. corporation)
PI US 5109089 19920428
AI US 1991-720927 19910625 (7)
RLI Division of Ser. No. US 1988-286472, filed on 19 Dec 1988, now
patented,

Pat. No. US 5057587
PRAI DE 1987-3743993 19871223
DT Utility
FS Granted
LN.CNT 314
INCL INCLM: 526/273.000
INCLS: 525/528.000; 525/530.000; 525/532.000
NCL NCLM: 526/273.000
NCLS: 525/528.000; 525/530.000; 525/532.000
IC [5]
ICM: C08F024-00
EXF 526/273; 525/528; 525/530; 525/532
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L11 ANSWER 3 OF 6 USPATFULL
AN 92:29770 USPATFULL
TI Hard transparent resins and process for the production thereof
IN Sasagawa, Katsuyoshi, Kanagawa, Japan
Kanemura, Yoshinobu, Kanagawa, Japan
Imai, Masao, Kanagawa, Japan
Suzuki, Toshiyuki, Kanagawa, Japan
PA Mitsui Toatsu Chemicals, Inc., Tokyo, Japan (non-U.S. corporation)
PI US 5104953 19920414
AI US 1989-362248 19890606 (7)
PRAI JP 1988-140484 19880609
DT Utility
FS Granted
LN.CNT 917
INCL INCLM: 526/301.000
NCL NCLM: 526/301.000
NCLS: 526/288.000
IC [5]
ICM: C08F026-02
EXF 526/301
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L11 ANSWER 4 OF 6 USPATFULL
AN 91:84530 USPATFULL
TI Radiation-curable liquid resin for secondary coating of lightwave guides
IN Birkle, Siegfried, Hoechststadt A/Aisch, Germany, Federal Republic of
Feucht, Hans-Dieter, Erlangen, Germany, Federal Republic of
Kamps, Rainer, Coburg, Germany, Federal Republic of
Rissel, Eva, Forchheim, Germany, Federal Republic of
PA Siemens Aktiengesellschaft, Berlin & Munich, Germany, Federal Republic of (non-U.S. corporation)
PI US 5057587 19911015
AI US 1988-286472 19881216 (7)
PRAI DE 1987-3743993 19871223
DT Utility
FS Granted
LN.CNT 306
INCL INCLM: 526/273.000
NCL NCLM: 526/273.000
IC [5]
ICM: C08F024-00
EXF 560/224; 560/160; 556/457; 526/273
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L11 ANSWER 5 OF 6 USPATFULL
AN 81:16451 USPATFULL
TI Photosensitive resin composition
IN Nagashima, Akira, Shizuoka, Japan
Sato, Shigeru, Odawara, Japan
PA Fuji Photo Film Co., Ltd., Minami-ashigara, Japan (non-U.S. corporation)

PI US 4258123 19810324
 AI US 1979-70556 19790829 (6)
 PRAI JP 1978-105196 19780829
 DT Utility
 FS Granted
 LN.CNT 723
 INCL INCLM: 430/281.000
 INCLS: 430/283.000; 430/284.000; 430/285.000; 430/286.000; 430/343.000;
 430/344.000; 430/916.000; 430/920.000; 430/925.000; 430/292.000
 NCL NCLM: 430/281.100
 NCLS: 430/283.100; 430/284.100; 430/285.100; 430/286.100; 430/292.000;
 430/343.000; 430/344.000; 430/916.000; 430/920.000; 430/925.000;
 522/016.000; 522/026.000; 522/034.000; 522/121.000
 IC [1]
 ICM: G03C001-68
 EXF 430/916; 430/920; 430/925; 430/343; 430/344; 430/281; 430/283; 430/285;
 430/284; 430/286; 430/292; 430/287; 430/288
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L11 ANSWER 6 OF 6 CAPLUS COPYRIGHT 2003 ACS

AN 1990:199852 CAPLUS

DN 112:199852

TI Hard transparent resins from monomers containing [(isopropenyl-
 .alpha.,.alpha.-dimethylbenzyl)amino]carbonyl groups

IN Sasagawa, Katsuyoshi; Kanemura, Yoshinobu; Imai, Masao; Suzuki, Toshiyuki

PA Mitsui Toatsu Chemicals, Inc., Japan

SO Eur. Pat. Appl., 37 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

| | PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------|-----------------------------------|------|----------|-----------------|----------|
| PI | EP 345748 | A2 | 19891213 | EP 1989-110275 | 19890607 |
| | EP 345748 | A3 | 19910515 | | |
| | EP 345748 | B1 | 19950426 | | |
| | R: CH, DE, FR, GB, IT, LI, NL, SE | | | | |
| | JP 02084406 | A2 | 19900326 | JP 1989-141203 | 19890605 |
| | JP 2641763 | B2 | 19970820 | | |
| | US 5104953 | A | 19920414 | US 1989-362248 | 19890606 |
| | AU 8936185 | A1 | 19891214 | AU 1989-36185 | 19890608 |
| | AU 605987 | B2 | 19910124 | | |
| | BR 8902738 | A | 19900201 | BR 1989-2738 | 19890609 |
| | CN 1040365 | A | 19900314 | CN 1989-106048 | 19890609 |
| | CN 1029851 | B | 19950927 | | |
| | US 5166285 | A | 19921124 | US 1992-835307 | 19920214 |
| | CN 1104648 | A | 19950705 | CN 1994-116091 | 19940919 |
| | CN 1104649 | A | 19950705 | CN 1994-116092 | 19940919 |
| | CN 1108667 | A | 19950920 | CN 1994-116093 | 19940919 |
| | CN 1065525 | B | 20010509 | | |
| PRAI | JP 1988-140484 | A | 19880609 | | |
| | US 1989-362248 | A3 | 19890606 | | |

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|---|-------|------------------|
| 1 | 1396 | ((528/60) or (528/61) or (528/63) or (528/64)).CCLS. | USPAT | 2003/06/02 11:17 |
| 2 | 259 | ((528/60) or (528/61) or (528/63) or (528/64)).CCLS.) and (thiol or mercap\$) | USPAT | 2003/06/02 11:19 |